

Form 1449 U.S. DEPARTMENT OF COMMERCE PATENT & TRADEMARK OFFICE LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				ATTY. DOCKET NO. M122-1398	SERIAL NO. 09/536,037		
				APPLICANT Weimin Li et al.			
				FILING DATE March 27, 2000	GROUP 2825 22		
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TMT	AA	6,054,379	04/25/00	Yau et al.	438	623	
	AB	5,948,482	09/07/99	Brinker et al.	427	430.1	
	AC	5,800,877	09/01/98	Maeda et al.	427	535	
	AD	5,260,600	11/09/93	Harada	257	639	
	AE	4,992,306	02/12/91	Hochberg et al.	427	255.3	
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
	AL						Yes
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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EXAMINER T. M. Thomas				DATE CONSIDERED 03/19/01			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

<p style="text-align: right;">O P E R A T I O N S - 1449 APR 30 2001 U. S. PATENT AND TRADEMARK OFFICE</p> <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>		U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1398	SERIAL NO. 09/536,037			
		APPLICANT Welmin Li et al.						
		FILING DATE March 27, 2000		GROUP 2822				
		U. S. PATENT DOCUMENTS						
*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
TMT	AA	6,017,778	01/25/00	Miyasaka		438	149	X
	AB	6,124,841	09/26/00	Matsuura		257	759	X
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	AD							
	AE							
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	AH							
	AI							
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country		Class	Subclass	Translation
TMT	AL	JP363157443A	30.08.88	Japan (Morita)		HOIL	21/90	Yes Abstract
	AM							
	AN							
	AO							
	AP							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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EXAMINER				DATE CONSIDERED				
T. M. Thomas				07-27-01				
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Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICELIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

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#13

ATTY. DOCKET NO.	SERIAL NO.
MI22-1398	09/536,037
APPLICANT	
Weimin (Michael) Li et al.	
FILING DATE	GROUP
March 27, 2000	2822

U.S. PATENT DOCUMENTS

Examiner	Document Number	Date	Name	Class	Subclass	Filing Date, If Appropriate
TMT	AA 4,474,975	10-2-1984	Clemons et al.	556	410	
	AB 5,962,581	10-5-1999	Hayase et al.	524	588	
	AC 4,805,683	2-21-1989	Magdo et al.	216	40	
	AD 5,874,367	2-23-1999	Dobson	438	787	
	AE 5,858,880	1-12-1999	Dobson et al.	438	758	
	AF 5,219,613	6-15-1993	Fabry et al.	438	758	
	AG 5,270,267	12-14-1993	Ouellet	438	597	
	AH 5,541,445	7-30-1995	Quellet	438	761	
	AI 6,022,404	2-8-2000	Ettlinger et al.	106	404	
	AJ 5,709,741	1-20-1998	Akamatsu et al.	106	287,11	
	AK 4,648,904	3-10-1987	DePasquale et al.	106	2	
	AL 4,158,717	6-19-1979	Nelson	428	446	
	AM 5,667,015	9-16-1997	Harestad et al.	166	383	
	AN 5,661,093	8-26-1997	Ravi et al.	438	763	
	AO 5,536,857	7-16-1996	Narula et al.	556	10	
	AP 4,695,859	9-22-1987	Guha et al.	257	64	
	AQ 5,061,509	10-29-1991	Naito et al.	427	497	
	AR 4,600,671	7-15-1986	Saitoh et al.	430	57.5	
	AS 5,753,320	5-19-1998	Mikoshiba et al.	427	572	
	AT 5,356,515	10-18-1994	Tahara et al.	438	715	
	AU 4,954,867	9-4-1990	Hosaka	257	639	
	AV 5,674,356	10-7-1997	Nagayama	438	694	
	AW 5,731,242	3-24-1998	Parat et al.	438	586	
TMT	AX 5,741,721	4-21-1998	Stevens	438	396	

EXAMINER

T. M. Thomas

DATE CONSIDERED

12-07-01

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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin (Michael) Li et al.		
# 13				FILING DATE March 27, 2000		GROUP 2822
U.S. PATENT DOCUMENTS						
EXAMINER'S Initials	Document Number	Date	Name		Class	Subclass
TMT	AA 5,376,591	12-27-1994	Maeda et al.		438	761
	AB 5,817,549	10-6-1998	Yamazaki et al.		438	166
	AC 6,001,741	12-14-1999	Afers		438	706
	AD 6,072,227	6-6-2000	Yau et al.		257	642
TMT	AE 6,786,039	7-28-1998	Brouquet		407	578
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				APPLICANT Weimin (Michael) Li et al.		FILING DATE March 27, 2000		GROUP 2822
FOREIGN PATENT DOCUMENTS								
Examiner's Initials		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
TMT	AA	06067019A	9/1999	Japan (Glass)(Abstract)				
	AB	6-244172	9/1994	Japan				
	AC	593,727	10/1947	GB				
	AD	5-263255	10/1993	Japan				
	AE	0 471 185 A2	7/10/91	EPO				
	AF	0 588 087 A2	8/18/93	EPO				
	AG	0 588 087 A3	8/18/93	EPO				
	AH	09055351	25/2/97	Japan				
	AI	0 778 496 A2	05/12/96	EPO				
	AJ	20029	US99	Search Report				
	AK	20030	US99	Search Report				
TMT	AL	0 942330	9-99	EPO (Joubert)				
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			FILING DATE March 27, 2000	GROUP 2822	
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)					
Examiner's Initials TMT			Name		
	AA		TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10. (No date)		
	AB		TEXT: Wolf, S. et al., "Silicon Processing for the VLSI Era", Vol. I, pp. 437-441. (No date)		
	AC		D.R. McKenzie et al., "New Technology for PACVD", Surface and Coatings Technology, 82 (1996), pp. 326-333.		
	AD		S. McClatchie et al.; "Low Dielectric Constant Flowfill® Technology For IMD Applications"; undated; 7 pages		
	AE		K. Beekmann et al.; "Sub-micron Gap Fill and In-Situ Planarisation using Flowfill™ Technology"; October 1995; pp. 1-7		
	AF		A. Kiermasz et al.; "Planarisation for Sub-Micron Devices Utilising a New Chemistry"; Electrotech, February 1995; 2 pages		
	AG		IBM Technical Disclosure Bulletin "Low-Temperature Deposition of SiO ₂ , Si ₃ N ₄ or SiO ₂ -Si ₃ N ₄ ", Vol. 28, No. 9, p. 4170, Feb. 1986.		
	AH		ARTICLE: Bencher, C. et al., "Dielectric antireflective coatings for DUV lithography", Solid State Technology (March 1997), pp.109-114.		
	AI		Noboru Shibata, "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Japanese Journal of Applied Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.		
	AJ		Ralls, Kenneth M., "Introduction to Materials Science and Engineering", John Wiley & Sons, © 1976, pp. 312-313		
	AK		Ravi K. Laxman, "Synthesizing Low-k CVD Materials for Fab Use", Semiconductor International, Nov. 2000, 10 pps.		
	AL		Anonymous, "New gas helps make faster IC's", Machine Design Cleveland, © Penton Media, Inc., November 4, 1999, pp. 118		
	AM		Loboda et al., "Using Trimethylsilane to Improve Safety Throughput and Versatility in PECVD Processes", 4th International Symposium on Silicon Nitride and Silicon Dioxide Thin Insulating Films, The Electrochemical Society, Abstract No. 358, p. 454. May 1997.		
	AN		ARTICLE: Dammel, R. R. et al., "Dependence of Optical Constants of AZ® BARLi™ Bottom Coating on Back Conditions", SPIE Vol. 3049 (1997), pp. 963-973.		
	AO		TEXT: Heavens, O. S., "Optical Properties of Thin Solid Films", pp. 48-49.		
	AP		Withmail, R. et al., "Matrix Reactions of Methyisilanes and Oxygen Atoms", Phys. Chem 1988, pp. 594-602.		
	AQ		Weidman, T. et al., "New photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers", Appl. Phys. Lett 1-25-93, pp. 372-374.		
	AR		Weidman, et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon Dioxide Precursor", Journal of Photopolymer Science and Technology, V. 8, #4, 1995, pp. 679-686.		
	AS		Joubert et al., "Application of Plasma Polymerized Methylsilane in an all dry resist process for 193 and 248 nm Lithography", Microelectronic Engineering 30 (1996), pp. 275-278.		
	AT		Joshi, A.M. et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography", SPIE Vol. 1925, pp. 709-720.		
	AU		Matsuura, M. et al., "Highly Reliable Self-Planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects", IEEE 1997, pp. 785-788.		
TMT	AV		Horie, O. et al., "Kinetics and Mechanism of the Reactions of ..., J. Phys. Chem 1991, 4393-4400.		
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O P E SEP 04 2001		LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT WEIMIN LI ET AL.				
				FILING DATE FILED HEREWITH	GROUP 3822			
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
TMT	AA	09/146,843	09/1998	LI ET AL.			09/03/1998	
TMT	AB	09/030,618	02/1998	YIN ET AL. NOW 6,274,292	430	313	02/25/1998	
TMT	AC	09/146,842	09/1998	YIN ET AL. NOW 6,281,100	438	585	09/03/1998	
TMT	AD	09/234,233	01/1999	LI ET AL.			01/20/1999	
TMT	AE	09/200,035	11/1998	LI NOW 6,156,674			11/25/1998	
TMT	AF	09/219,041	12/1998	LI ET AL.			12/23/1998	
TMT	AG	4,833,096	05/1989	HUANG ET AL.	437	43		
TMT	AH	5,405,489	04/1995	KIM ET AL.	156	643		
TMT	AI	5,470,772	11/1995	WOO	437	43		
TMT	AJ	5,652,187	07/1997	KIM ET AL.	437	240		
TMT	AK	5,656,337	08/1997	PARK ET AL.	427	539		
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
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	AM							
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	AO							
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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EXAMINER T. M. Thomas				DATE CONSIDERED 12-17-01				
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1393	SERIAL NO. FILED HEREWITH		
O I P E SEARCHED INDEXED MAILED SEP 04 2001		LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT WEIMIN LI ET AL.			
				FILING DATE FILED REREWITH	GROUP 2802		
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TMT	AA	09/146,843 ✓	09/1998	LI ET AL.			09/03/1998
TMT	AB	09/030,618 ✓	02/1998	YIN ET AL. <i>now 6,274,292</i>	430	313	02/25/1998
TMT	AC	09/146,842 ✓	09/1998	YIN ET AL. <i>now 6,281,100</i>	438	585	09/03/1998
TMT	AD	09/234,233 ✓	01/1999	LI ET AL. <i>now 7,235,499</i>			01/20/1999
TMT	AE	09/200,035 ✓	11/1998	LI <i>now 6,156,674</i>			11/25/1998
TMT	AF	09/219,041 ✓	12/1998	LI ET AL.			12/23/1998
TMT	AG	4,833,096 ✓	05/1989	HUANG ET AL.	437	43	
TMT	AH	5,405,489 ✓	04/1995	KIM ET AL.	156	643	
TMT	AI	5,470,772 ✓	11/1995	WOO	437	43	
TMT	AJ	5,652,187 ✓	07/1997	KIM ET AL.	437	240	
TMT	AK	5,656,337 ✓	08/1997	PARK ET AL.	427	539	
FOREIGN PATENT DOCUMENTS							
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TMT	AL	09-050993 <i>checkmark</i>	03/1997	JAPAN (MITSURU)	007	135	Abstract
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT WEIMIN LI ET AL.			
SEP 04 2001					FILING DATE FILED HEREWITH		GROUP 3822	
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
TMT	AA	5,677,015	10/1997	HASEGAWA		427	576	
	AB	5,783,493	07/1998	YEH ET AL.		438	718	
	AC	5,807,660	09/1998	LIN ET AL.		430	313	
	AD	5,744,399	04/1998	ROSTOKER ET AL.		438	622	
	AE	6,028,015	02/2000	WANG ET AL.		438	789	
	AF	5,461,003	10/1995	HAVEMANN ET AL.		438	666	
	AG	5,883,014	03/1999	CHEN ET AL.		438	780	
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		Document Number	Date	Country	Class	Subclass	Translation	
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MI22-1398SERIAL NO.
09/536,037LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary) #14APPLICANT
Weimin (Michael) Li et al.FILING DATE
March 27, 2000GROUP
2822

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

Examiner's
Initials

Name

AA Julius Grant, Black's Chemical Dictionary, Fourth Edition, McGraw-Hill Book Company, © 1969,
revised by Grant © 1972, pp. 27

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LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

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OCT 18 2001

APPLICANT
Weimin Li et al.FILING DATE
March 27, 2000GROUP
2822

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TMT	AA	6,235,568 B1	5/01	Murthy et al.	438	231	
	AB	6,187,694 B1	2/01	Cheng et al.	438	251	
	AC	5,750,442	5/98	Juengling	438	761	
	AD	6,114,255	9/00	Juengling	438	763	
	AE	6,238,976	5/01	Noble et al.	438	259	RECEIVED MAY 22 2001 U.S. PATENT AND TRADEMARK OFFICE
	AF	6,008,121	12/99	Yang et al.	438	637	RECEIVED MAY 22 2001 U.S. PATENT AND TRADEMARK OFFICE
	AG	5,140,390	8/92	Li et al.	357	350	RECEIVED MAY 22 2001 U.S. PATENT AND TRADEMARK OFFICE
	AH	5,286,661	2/94	de Fresari et al.	438	343	RECEIVED MAY 22 2001 U.S. PATENT AND TRADEMARK OFFICE
	AI	6,184,151	2/01	Adair et al.	438	743	
	AJ	6,225,217 B1	5/01	Usami et al.	438	637	
	AK	6,004,850	12/99	Lucas et al.	438	301	
	AL	6,140,677	10/00	Gardner et al.	357	327	
	AM	6,133,096	10/00	Su et al.	438	264	
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	AR	6,130,168	10/00	Chu et al.	438	717	
	AS	6,235,591	5/01	Balasubramanian et al.	438	275	
TMT	AT	6,198,144 B1	3/01	Pan et al.	257	412	
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T. M. Thomas

DATE CONSIDERED

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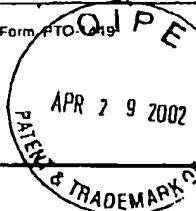
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Sheet 1 of 1

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE FEB 11 2002 11/07/02 PTO-140 U.S. PATENT & TRADEMARK OFFICE COPY OF ART CITED BY APPLICANT (Use several sheets if necessary)				ATTY. DOCKET NO. M122-1398	SERIAL NO. 09/536,037	
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U.S. PATENT DOCUMENTS						
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TMT	AA 6,268,282 B1	07/31/01	Sundhu et al.	438	636	
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		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. I.C. MI22-1398	SERIAL NO. 10558012		
		ART OF ART CITED BY APPLICANT (Use several lines if necessary) COPY OF PAPERS ORIGINALLY FILED		APPLICANT Weimin (Michael) Li et al.	FILING DATE March 27, 2000	GROUP 2822	
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	AB	5,543,654	08/06/1996	Dennen	257	386	
	AC	5,656,330	08/12/1997	Niiyama et al.	427	255,395	
	AD	5,872,035	02/16/1999	Kim et al.	438	261	
	AE	4,444,617	04/24/1984	Whitcomb	438	721	
	AF	6,071,799	06/06/2000	Park et al.	438	595	
	AG	3,691,212	11/23/1997	Tsai et al.	438	297	
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TMT	AI	5,792,689	08/11/1998	Yeng et al.	438	253	
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		Document Number	Date	Country	Class	Subclass	Translation
							Yes
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OTHER REFERENCES (including Author, Title, Date, Pertinent Page, Etc.)							
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EXAMINER				DATE CONSIDERED			
T. M. Thomas				08-05-02			
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin (Michael) Li et al.			
# 35				FILING DATE March 27, 2000	GROUP 2822		
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TMT	AA 6,451,504 B2	09/17/02	Rolfson et al. (Previously cited as 09/773,462)		430	272,11	
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EXAMINER	T. M. Thomas		DATE CONSIDERED 12/15/02				
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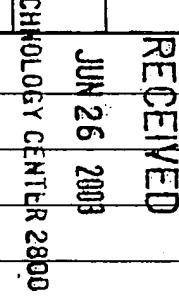
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/	N	EP 1 172 845 A2	01-2002	EP	—	H01L 21/3105
/	O	JP 08-213386 A	08-1996	JP	Kudo et al.	H01L 21/316
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		# 39		APPLICANT Weimin (Michael) Li et al.	
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TMT	4,562,091	12/31/85	Sachdev et al.	427	489
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EXAMINER	T. M. Thomas		DATE CONSIDERED 04-02-03		
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 LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		#43		APPLICANT: Li et al.			
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TMT	AA	5,986,318	11/16/99	Kim et al.	257 437		
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Weimin Li, et al.		
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TMT	AM	08-045926A	02/1996	Japan			No
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TMT	AR	Wolf, S., Silicon Processing for the VLSI ERA. Vol. 3, The Submicron MOSFET p. 635					
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EXAMINER			DATE CONSIDERED				
T. M. Thomas			02/06/05				
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 LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT: Li et al.			
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JMJ	AA	6,121,133	09/19/00	Iyer et al.	438	636		
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EXAMINER J. M. Thomas		DATE CONSIDERED 12-08-05						
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Welmin Li et al.					
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		Document Number	Date	Country	Class	Subclass	Translation
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